The SLS Optics Beamline – Performance Measurements and Status

U. Flechsig

Paul Scherrer Institut, Villigen, Switzerland

Actop workshop, Trieste, Oct 2008

U. Flechsig Actop workshop, Oct 2008

イロト イポト イヨト イヨ

Outline

- Status
 - The Swiss Light Source SLS
 - Optics Beamline X05DA
- Performance Measurements
 - Photon Flux
 - Higher Orders
 - Focus
 - Pink Beam

3 Hardware

- Monochromator Assembly
- Mirror Bender



Applications

Conclusions

SLS Optics

The SLS as Part of the PSI



U. Flechsig

Actop workshop, Oct 2008

SLS Optics

SLS Parameters

Parameter:

- circumference: 288 m
- electron energy: 2.4 GeV
- typical current: (400 ± 0.5) mA
- 9 straights for ID's, 9 ID-BL's in operation, 2 in construction
- about 24 BM-BL's possible, 8 in operation, 1 in construction
- Is slicing facility at X05L



SLS Optics

The Optics Beamline X05DA





- photon energy: 5.5 ... 22.5 keV (with mono)
- different modes: monochromatic, pink beam, focused, unfocused

・ロト ・回ト ・ヨト ・ヨト

Photon Flux Higher Orders Focus Pink Beam

Statu

The Swiss Light Source SLSOptics Beamline X05DA

Performance Measurements

- Photon Flux
- Higher Orders
- Focus
- Pink Beam

Hardware

- Monochromator Assembly
- Mirror Bender

Applications

5 Conclusions



Photon Flux Higher Orders Focus Pink Beam

Monochromatic Photon Flux



photon flux in photons/s, $E/\Delta E \approx 3000$, uncalibrated AXUV100 photo diode: area 1 cm², hor. acceptance 1 mrad (1) and 0.6 mrad (2).

Photon Flux Higher Orders Focus Pink Beam

Higher Orders and Focus





Photon Flux Higher Orders Focus Pink Beam

Higher Orders and Focus





イロト 不得 とくほと くほう

Photon Flux Higher Orders Focus Pink Beam

Dynamic Focusing with Mirror Bender (1)

X05DA dynamic focusing

images @ 16.5 m, 12 keV



nominal (vertical) focus position (m)

・ロト ・回ト ・ヨト ・

14.8	15.8	16.8	17.8	18.8	19.8	
1.9	2.0	2.1	2.2	2.3	2.4	
				mirror radius (km)		

file: fxv.fig

Photon Flux Higher Orders Focus Pink Beam

Dynamic Focusing with Mirror Bender (2)



U. Flechsig

Actop workshop, Oct 2008

Photon Flux Higher Orders Focus Pink Beam

Focus Stability during Energy Scan



U. Flechsig

Actop workshop, Oct 2008

Photon Flux Higher Orders Focus Pink Beam

Pink Beam

unfocused pink beam



focused pink beam 100 μm Kapton window melts within a few s, estimated power density: $1.6 \, \mathrm{kW/mm^2}$

measurement with thermopile sensor: 10.6 W for 1 mrad FE opening

Photon Flux Higher Orders Focus Pink Beam

Pink Beam

unfocused pink beam



measurement with thermopile sensor: 10.6 W for 1 mrad FE opening

focused pink beam



100 μ m Kapton window melts within a few s, estimated power density: $1.6 \, \mathrm{kW/mm^2}$

Status

- The Swiss Light Source SLS
- Optics Beamline X05DA

Performance Measurements

- Photon Flux
- Higher Orders
- Focus
- Pink Beam

3 Hardware

- Monochromator Assembly
- Mirror Bender

Applications

5 Conclusions

Monochromator Assembly



Mirror Bender





・ロト ・回ト ・ヨト ・ヨト



æ

Glueing Tests

Status

- The Swiss Light Source SLS
- Optics Beamline X05DA

Performance Measurements

- Photon Flux
- Higher Orders
- Focus
- Pink Beam

3 Hardware

Monochromator Assembly

<ロト <四ト <注入 <注下 <注下 <

Mirror Bender

Applications

Conclusions



An ultrafast streak camera for the detection of hard x-ray synchrotron radiation



Details

courtesy Maik Kaiser Sep 2008



- very flexible beamline, reliable operation, good performance, very economic realization
- offers fast beam access for instrumentation developments and detector calibration
- possibility to exploit the beamline for at wavelength metrology and optics characterization is foreseen

▲ @ ▶ ▲ ⊇ ▶

Acknowledgment

- SLS optics group
 - Sibylle Spielmann
 - Andreas Jaggi
 - Veit Schönherr (now Jenoptik)
- Advanced Light Source
 - Howard Padmore
 - Alastair McDowell
 - Keith Franck

- PSI engineering
 - Sasa Zelenika (now Univ. Rijeka)
 - Hansueli Walther
 - Charles Zumbach
 - Heinrich Blumer
- SLS controls
 - Werner Portmann

ヘロト ヘアト ヘヨト ヘ



I thank you for your attention!



Streaked hybrid pulse



Streaked hard x-ray pulse (100 ps) at 12 keV with gated MCP technology (100 ns gate @ 1 kHz)

The estimated time resolution of the apparatus at this stage is about 2ps.

I Return

courtesy Maik Kaiser Sep 2008

(日)、

Learning the Bonding Technology and Tests

topics: surface treatment handling etc.











silicon breaks at F > 20000 N(area: 60 × 50 mm)

イロト イポト イヨト イヨ



